

Atomic structure of the reconstructed $\text{Al}_2\text{O}_3(0001)$ surface

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Corundum $\alpha\text{-Al}_2\text{O}_3$ is an important ceramic widely used in electronics, optical applications, or as catalyst support. Despite its importance, the atomic structure of the most stable (0001) termination has not been conclusively determined. Detailed studies of Al_2O_3 surfaces have been stymied by its insulating nature, preventing the use of many surface science methods.

Structural models based on surface X-ray diffraction (SXRD) [1], and atomic force microscopy (AFM) [2], concluded the $(\sqrt{31} \times \sqrt{31})\text{R}\pm 9^\circ$ -reconstructed $\text{Al}_2\text{O}_3(0001)$ surface formed upon high-temperature annealing is terminated by one or two layers of metallic Al strained to lattice-match the oxide substrate.

We imaged the reconstructed $\text{Al}_2\text{O}_3(0001)$ surface with noncontact AFM (nc-AFM) using specifically functionalized tips for chemically-sensitive contrast. In particular, CuO_x terminated tips [3], enabled us to directly identify oxygen and aluminum atoms in the topmost layer.

With the aid of *ab-initio* calculations, we propose a structural model of the $(\sqrt{31} \times \sqrt{31})\text{R}\pm 9^\circ$ -reconstructed $\text{Al}_2\text{O}_3(0001)$ surface consistent with atomically resolved nc-AFM images and area-averaging spectroscopic data. Unlike prior models, the surface does not contain a metallic Al layer but consists of oxygen and aluminum atoms arranged in similar structural units as reported in thin AlO_x films [4,5].

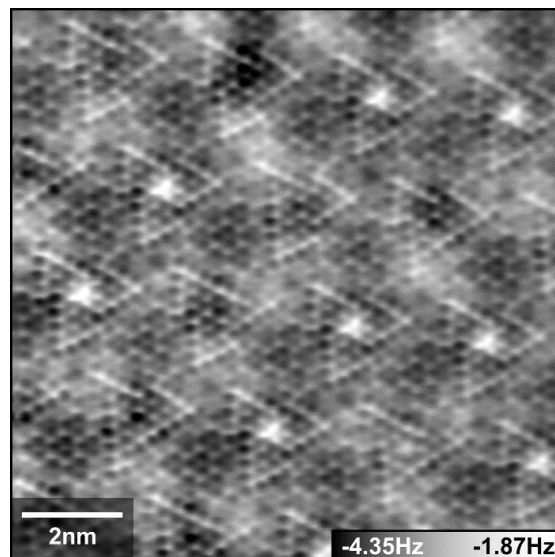


Fig. 1. NC-AFM image of $(\sqrt{31} \times \sqrt{31})\text{R}\pm 9^\circ$ -reconstructed $\text{Al}_2\text{O}_3(0001)$ acquired with a CuO_x -terminated tip.

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[3] B. Shulze Lammers, et al., *Nanoscale* **13**, 13617 (2021)

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